



## PATENT ABSTRACTS OF JAPAN

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**HACHISUGA HISAO**(54) **PURE WATER PRODUCING SYSTEM**

## (57) Abstract:

**PROBLEM TO BE SOLVED:** To keep the amount of filtrate from a reverse osmosis membrane module sufficiently stable irrespective the elution of polymeric organic substances from an ion exchange resin apparatus by forming a surface potential reducing thin film on the membrane surface of the module.

**SOLUTION:** An ion exchange resin apparatus 2 is installed in the preceding stage of a reverse osmosis membrane module 1, raw water is supplied to the apparatus 2 by a liquid sending pump 3, and deionized water from the apparatus 2 is stored in an intermedi-

ate tank 4. The liquid in the tank 4 is supplied to the module 1 by a liquid sending pump 5. In this process, to prevent the attraction of eluted organic substances from the apparatus 2 to the membrane surface of the module 1 by an electrical surface phenomenon, a surface potential reducing thin film is formed on the surface of the reverse osmosis membrane. In this way, pure water can be produced in a stable flow rate.

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